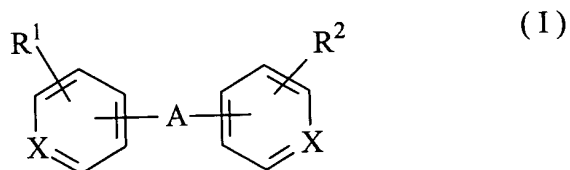


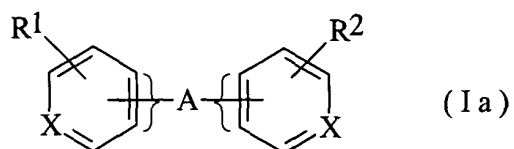
AMENDMENTS TO THE CLAIMS

1. (Currently Amended) A negative type resist composition comprising alkali soluble resin, acid generator, crosslinking agent, and a basic compound represented by the following formula (I)



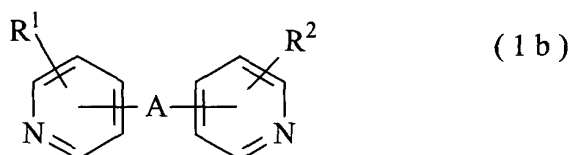
wherein, A represents sulfide group, disulfide group or bivalent aliphatic hydrocarbon residue which may be optionally interrupted by imino group, [sulfide group, or disulfide group,] X represents nitrogen atom or C(NH₂), and R¹ and R² independently represent hydrogen or alkyl provided that, when X represents C(NH₂), A represents sulfide group or disulfide group.

2. (Original) The negative type resist composition according to claim 1, wherein the basic compound of the formula (I) is represented by the following formula (Ia):



wherein, A, X, R¹ and R² are the same as defined in claim 1, and the marks, "}" and "{", indicate that A is positioned on 3-position, or 4-position on the six-membered rings with respect to X.

3. (Original) The negative type resist composition according to claim 1, wherein the basic compound of the formula (I) is represented by the following formula (Ib):



wherein, A, R¹ and R² are the same as defined in claim 1.

4. (Original) The negative type resist composition according to claim 3, wherein A is a linear alkylene having 2 to 4 carbon atoms, linear alkenylene having 2 to 4 carbon atoms or iminobisalkylene having 2 to 6 carbon atoms.

5. (Original) The negative type resist composition according to claim 4, wherein the basic compound of formula (Ib) is selected from 1,2-di(4-pyridyl)ethane, 1,3-di(4-pyridyl)propane, 1,2-di(4-pyridyl)ethylene and bis(3-pyridylmethyl)amine.

6. (Original) The negative type resist composition according to claim 3, wherein A is a sulfide group or a disulfide group.

7. (Original) The negative type resist composition according to claim 6, wherein the basic compound of formula (Ib) is selected from 4,4'-dipyridylsulfide and 4,4'-dipyridyldisulfide.

8. (Original) The negative type resist composition according to claim 1, wherein the alkali soluble resin is a polyvinyl phenol-based resin.

9. (Currently Amended) The negative type resist composition according to claim 1, wherein the acid generator [Is] is a sulfonic ester of N-hydroxyimide compound.

10. (Original) The negative type resist composition according to claim 1, wherein composition ratio of the basic compound of

formula (I) is between 0.02 and 1 wt %, based on the total solid content in the composition.

11. (Original) The negative type resist composition according to claim 1, wherein A is a linear alkylene having 2 to 4 carbon atoms, linear alkenylene having 2 to 4 carbon atoms or iminobisalkylene having 2 to 6 carbon atoms.

12. (Original) The negative type resist composition according to claim 1, wherein A is a sulfide group or a disulfide group.

13. (Original) The negative type resist composition according to claim 1, wherein A is selected from the group consisting of methylene, ethylene, vinylene, trimethylene, tetramethylene, iminobismethylene, sulfide and disulfide.